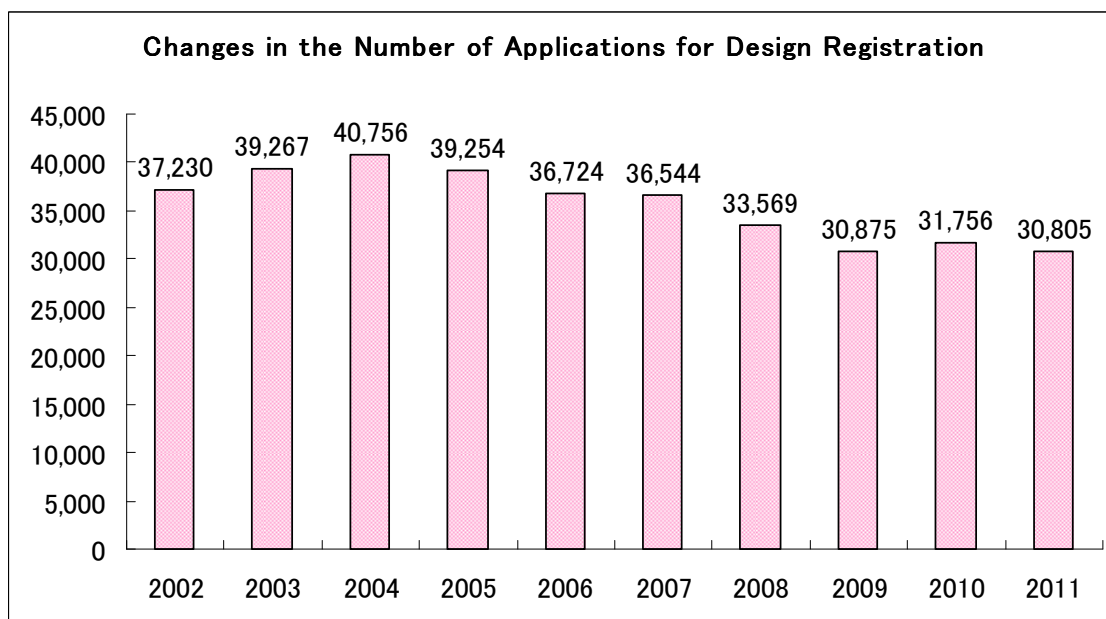


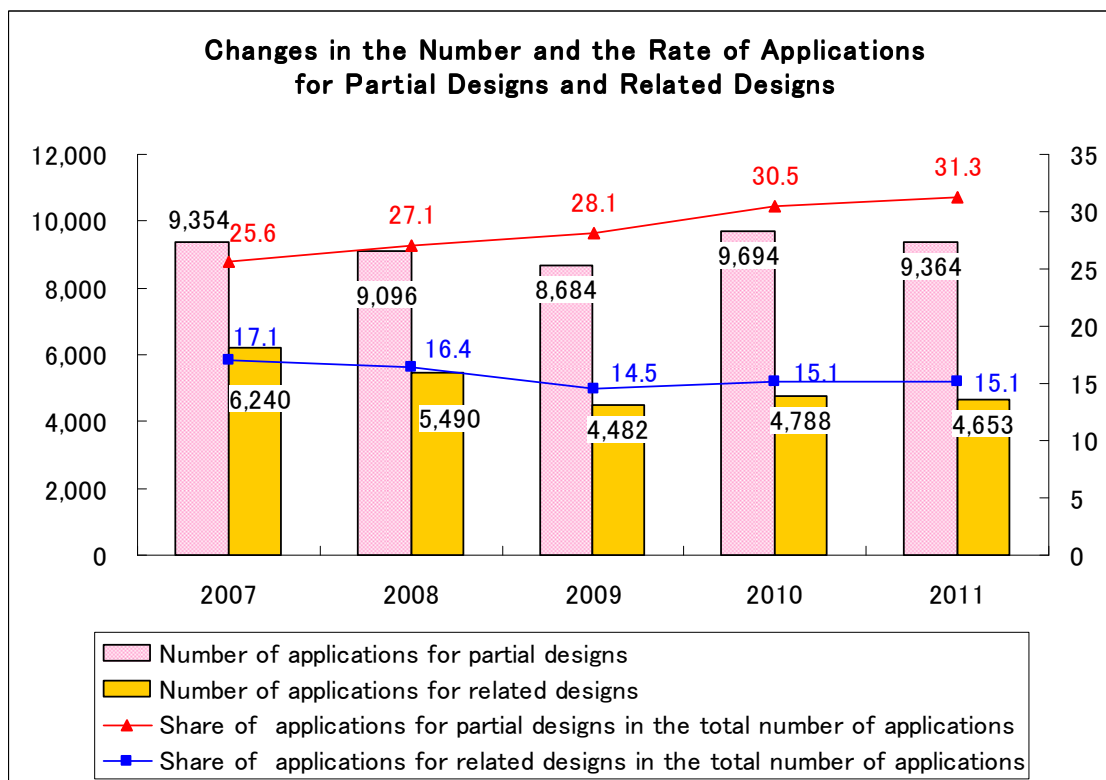
Newsletter / IP Japan

Current Situation of Design Registration In Japan

1. Statistics on Design Applications in Japan



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The changes in the number of applications after 2002 show a downward trend after the number reached its peak of 40,756 in 2004, but it almost remains unchanged for the latest 3 years (from 2009 to 2011). It is considered that the decline of the number of applications was attributable mainly to outward shift of applications by Japanese companies associated with the business expansion to overseas and the careful selection of filing applications.

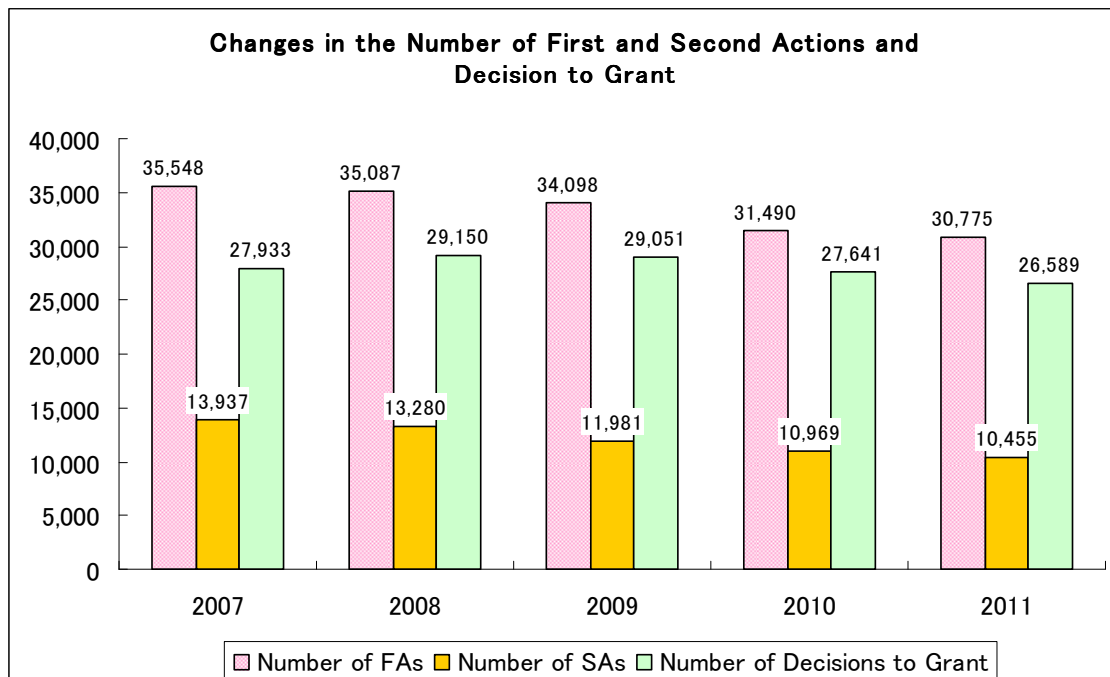
The rate of applications for partial designs in the total number of applications has been increasing since 1999, when the partial design system was introduced. It has accounted for more than 30 % of the total number of applications.

The rate of applications for the related design system, introduced in the same year, shows the downward trend before 2009. However, it remains unchanged in 2011 compared to the previous year.

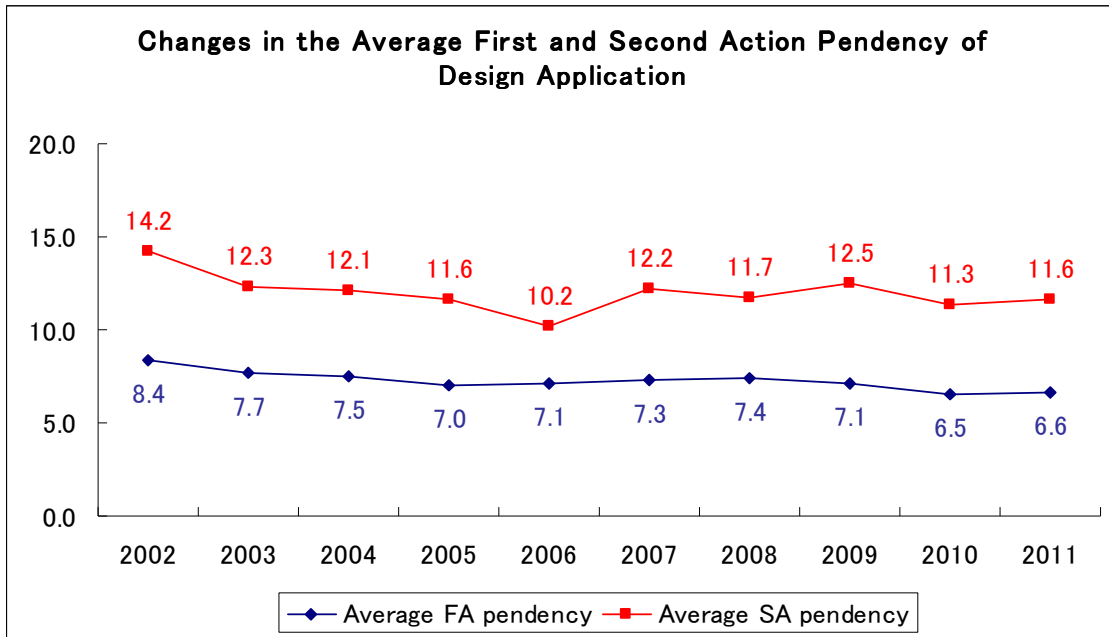
2. Statistics on Design Examination

The number of first actions (number of FAs) falls from 31,490 in 2010 to 30,755 in 2011. The average period from the filing date to the date when the first notice of examination results is issued (first action pendency or FA pendency) is 6.6 month. It shifts steadily compared to the 6.5 month in 2010.

The number of applications for which the decision following the first action is issued (number of SAs) is 10,455 in 2011. The average period from the filing date to the date when the decision following the first action is issued (SA pendency) is 11.6 months. The average number of design registrations has remained under 30,000 from 2007.

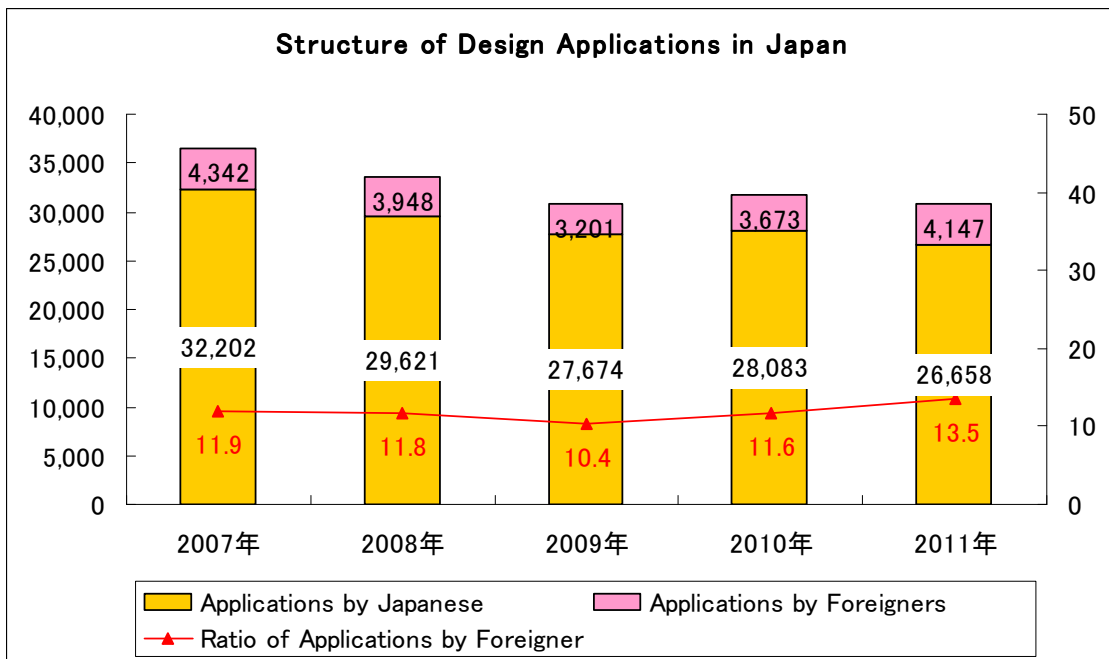


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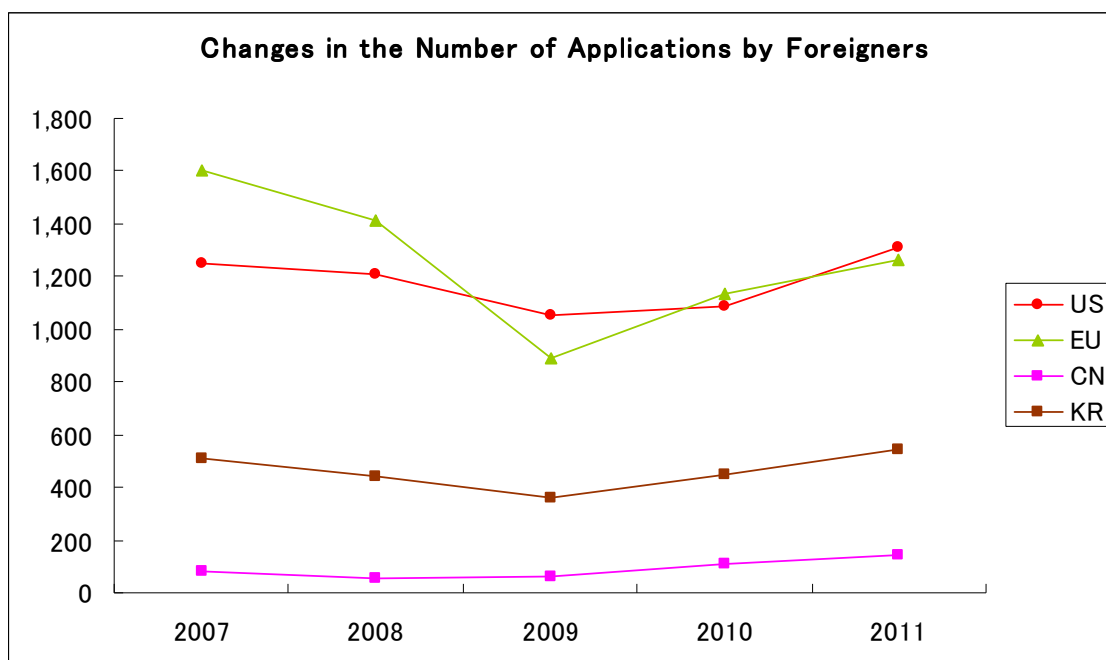


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3. Statistics on Applications Filed by Foreigners



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	2007	2008	2009	2010	2011	Proportion against a total
US	1,247	1,212	1,056	1,084	1,311	31.6%
EU	1,600	1,412	888	1,135	1,265	30.5%
China	81	57	62	111	144	3.5%
Korea	508	443	363	449	545	13.1%
Others	906	824	832	894	882	21.3%
Total	4,342	3,948	3,201	3,673	4,147	100.0%

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The number of domestic applications by Japanese reduces in 2011. On the other hand, the number of applications by foreigners increases. As a result, the rate of the number of applications by foreigners increases.

Although the number of design applications from US, EU and Korea to Japan drops temporarily in 2009, it has been upward trend since 2010. The number of design applications from China to Japan has been gradually increasing. However, it still records only 144 (it accounted 3.5 % of the total number of applications by foreigners) in 2011

4. Outcome of Trials for Invalidation

The number of trials for invalidation against Design registration				
Year	Number of request filed	Successful request*	Unsuccessful request**	Withdrawn/ Abandoned
2006	19	17	9	2
2007	24	13	5	3
2008	22	12	15	6
2009	15	6	8	0
2010	20	8	4	0
2011	16	11	4	2

* Registration is canceled. Including success-in-part request

** Registration is maintained. Including request which is dismissed without prejudice

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